Appl. No. 10/650,451 Amdt. dated January 26, 2011 Reply to Office Action of September 13, 2010

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings of claims in the application:

Listing of Claims:

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vertical electrical current path therebetween.

1	1. (Currently amended) A power device, comprising:
2	a semiconductor substrate of first conductivity having an upper surface and a
3	lower surface;
4	a first electrode terminal coupled to a first conductive region provided proximate
5	the upper surface of the substrate, the first electrode terminal being provided over the upper
6	surface of the substrate;
7	a second electrode terminal coupled to a second conductive region provided
8	proximate the lower surface of the substrate, the second electrode terminal being provided below
9	the lower surface of the substrate;
10	an isolation diffusion region of second conductivity provided at a periphery of the
11	substrate and extending from the upper surface to the lower surface of the substrate, the isolation
12	diffusion region having a first surface corresponding to the upper surface of the substrate and a
13	second surface corresponding to the lower surface;
14	a peripheral junction region of second conductivity formed at least partly within
15	the isolation diffusion region and formed proximate the first surface of the isolation diffusion
16	region; and
17	a passivation layer provided over the upper surface of the substrate, the first
18	surface of the isolation diffusion region, and the peripheral junction region, the passivation layer
19	comprising a polyimid layer [[over]] and an oxide layer;
20	wherein the peripheral junction region is different than the first conductive region
21	and the second conductive region[[s]], and
22	wherein the first <u>electrode terminal</u> and <u>the second electrode terminal[[s]]</u> define a

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- 2. (Original) The device of claim 1, wherein the peripheral junction region is a
 P+ region and the isolation diffusion region is a P region.
- 3. (Previously presented) The device of claim 1, wherein the peripheral junction
 region is provided to compensate the surface depletion of dopants in the isolation diffusion
 region.

4-25. (Canceled)

1 26. (Currently amended) The device of claim 1, wherein the passivation layer includes an oxide layer [[and]] contacts the upper surface of the substrate, the first surface of the isolation diffusion region, and the peripheral junction region.

27. (Canceled)

- 1 28. (Previously presented) The device of claim 1, wherein the peripheral
 2 junction region is provided to compensate the surface depletion of dopants in the isolation
 3 diffusion region and increase a reverse blocking voltage of the device by reducing an electric
 4 field at the first surface of the isolation diffusion region.
 - 29. (Canceled)
- 1 30. (Currently amended) The device of claim 1, wherein the device is a diode 2 and the first electrode terminal being separated is space apart from the isolation diffusion region.